S.N. 10/632,277

Date of Response: September 19, 2005

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Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

 (original) A high performance reflector system for use on scintillator elements contained in a scintillator array of a computed tomograph imaging system, the scintillator elements having a reflective material coupled along its surfaces defined within the gaps between scintillator elements, the reflective material comprising:

a smoothening layer,

a metallic reflective layer applied to said smoothening layer; and
a top layer applied to said metallic reflective layer, said top layer providing an
environmental barrier to said metallic reflective layer.

- 2. (original) The reflective material of claim 1, wherein said smoothening layer comprises an etched smoothening layer.
- 3. (original) The reflective material of claim 1 further comprising an adhesion layer applied between said smoothening layer and said metallic reflective layer.
- 4. (currently amended) The reflective material of claim 1, wherein said smoothening layer has a thickness of about 0.5.2 to 10 microns.
- 5. (original) The reflective material of claim 1, wherein said smoothening layer comprises a low viscosity polymer material, said polymer material being transparent to the emission wavelengths of said plurality of scintillator elements.
- 6. (currently amended) The reflective material of claim 5, wherein said low viscosity polymer material is selected from the group consisting of silicone hardcoats, styrene acrylate

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coatings, ultraviolet curable handcoats, Epotek, Hysul®, transparent low refractive index epoxy materials, and Saran oligomer coatings polyvinylidene chloride

- 7. (original) The reflective material of claim 3, wherein said adhesion layer has a thickness of less than about 200 Angstroms.
- 8. (original) The reflective material of claim 3, wherein said adhesion layer is selected from the group consisting of a titanium adhesion layer, an aluminum adhesion layer, a tungsten adhesion layer, a chromium adhesion layer, and a zirconium adhesion layer.
- 9. (original) The reflective material of claim 1, wherein said metallic reflective layer has a thickness of at least 500 Augstroms.
- 10. (original) The reflective material of claim 1, wherein said metallic reflective layer has a thickness of between about 2000 and 3000 Angstroms.
- 11. (original) The reflective material of claim 1, wherein said metallic reflective layer is selected from the group consisting of a silver reflective layer, a gold reflective layer, a copper reflective layer, a chodium reflective layer, a magnesium reflective layer, and an aluminum reflective layer.
- 12. (original) The reflective material of claim 1, wherein said top layer comprises a barrier coating layer applied to a thickness of at least 500 Anystroms.
- 13. (original) The reflective material of claim 1, wherein said top layer comprises a barrier coafing layer applied to a thickness of between about 1000 and 5000 Angstroms.
- 14. (original) The reflective material of claim 1, wherein said top layer comprises a barrier coating layer, said barrier coating layer selected from the group consisting of a metallic barrier coating layer, an inorganic barrier coating layer, and a ceramic barrier coating layer.
- 15. (currently amended) The reflective material of claim 14, wherein said top layer further comprising comprises a polymeric encapsulant applied to said barrier coating layer.

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- 16. (original) The reflective material of claim 15, wherein said polymeric encapsulant has a thickness of between approximately 5 and 10 micrometers.
- 17. (currently amended) The reflective material of claim 15, wherein said polymeric encapsulant is selected from the group consisting of a ultraviolet cured hardcost, a styrene acrylate encapsulant, a Saran oligomer polyvinylidene chloride encapsulant, and an amorphous polytetrafluoroethylene encapsulant.
- 18. (original) The reflective material of claim 1, wherein said top layer comprises a polymeric encapsulant having a thickness of between approximately 5 and 10 micrometers.
- 19. (currently amended) The reflective material of claim 18, wherein said polymeric encapsulant is selected from the group consisting of a ultraviolet cured hardcoat, a styrene acrylate encapsulant, a Saran oligomer polyvinylidene chloride encapsulant, and an amorphous Teffon polytetrafluoroethylene encapsulant.
- 20. (currently amended) A method for forming a high performance reflector for a scintillator array used in a computed tomograph imaging system, the high performance reflector having a plurality of scintillator elements formed in an array, the method comprising:

applying a smoothening coating layer to a top surface and to each of four adjacent side surfaces of each of said plurality of scintillator elements;

optionally etching said smoothening layer;

optionally applying an adhesion layer to said smoothening layer;

applying a metallic reflective layer to said adhesion layer, and

applying a top layer to said metallic reflective layer, said top layer providing
an environmental barrier to said metallic reflective layer.

21. (currently amended) The method of claim 20, wherein applying a smoothening layer comprises spin coating said surface with a low viscosity polymer material, said low viscosity polymer material being selected from the group consisting of silicone hardcoats, styrene

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acrylate coatings, ultraviolet curable hardcoats, Epotek, Hysol®, transparent low refractive index cpoxy materials, and Saran oligomer coatings pulyvinylidene chloride.

- 22. (original) The method of claim 20, wherein optionally etching said smoothening layer comprises optionally argon plasma etching said smoothening layer.
- 23. (original) The method of claim 20, wherein applying said metallic reflective layer comprises sputtering said metallic reflective layer onto said smoothening layer.
- 24. (original) The method of claim 20, wherein applying said metallic reflective layer comprises depositing said metallic reflective layer onto said smoothening layer using a chemical vapor deposition technique.
- 25. (original) The method of claim 20, wherein applying said metallic reflective layer comprises depositing said metallic reflective layer onto said smoothening layer using a physical vapor deposition technique.
- 26. (original) The method of claim 20, wherein applying said metallic reflective layer comprises depositing said metallic reflective layer onto said smoothening layer using a chemical reduction from a liquid phase technique.
- 27. (original) A scintillator for use in a computed tomograph application comprising:
- a plurality of scintillator elements formed into an array, each of said plurality of scintillator elements having a top surface and four adjacent side surfaces;
- a smoothening layer applied to said top surface and to each of said four adjacent side surfaces; and
- a metallic reflective coating applied to said smoothening layer, said metallic reflective coating formed from a reducing agent and a metal complex.
- 28. (original) The scintillator of claim 27, wherein said metal complex comprises a silver amine complex.

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29. (original) The scintillator of claim 27, wherein said metal complex is selected from the group consisting of a gold cyanide complex and a gold thiosulfate complex.

- 30. (original) The scintillator of claim 27, wherein said metal complex comprises a rhodium metal complex.
- 31. (original) The scintillator of claim ZI, wherein said reducing agent comprises an aqueous solution of glucose.
- 32. (original) The scintillator of claim 27, wherein said reducing agent comprises an aqueous solution of a Rochelle sait.
- 33. (original) The scintillator of claim 27, wherein said metal complex comprises a copper amine complex.
- 34. (original) A method for forming a high performance reflector for a scintillator array used in a computed tomograph imaging system, the scintillator array having a plurality of scintillator elements, the method comprising:

applying a smoothening coating to a top surface and to each of four adjacent side surfaces of each of said plurality of scintillator elements;

applying a reducing agent to said smoothening coating;

degassing said reducing agent;

applying a metal complex solution to said reducing agent layer to form a metal reflecting layer; and

washing and drying said metal reflecting layer.

35. (original) The method of claim 34, wherein said reducing agent comprises an aqueous solution of glucose.

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- 36. (original) The method of claim 34, wherein said reducing agent comprises an aqueous solution of a Rochelle salt.
- 37. (currently amended) The method of claim 34, wherein said reducing agent solution and said metal complex solution are mixed to form a mixture prior to applying said reducing agent and said metal complex solution to said adjacent surfaces within said gap smoothening coating.